

**Attachment 1**  
**Contract Line Item Numbers**

Item No.            Description

Base Year:

0001    Photolithographic reticles for GCA XLS Model 7300 I-line stepper, consisting of:

    0001AA Reticle, 0.090 inch thick, including data fracture of up to 4 die per layer, defect inspection and repair, barcode generation. 2.0 micron minimum critical dimension, tolerance  $\pm 0.25$  micron, range 0.25 micron, address size 0.20 micron, registration  $\pm 0.25$  micron.

    0001AB Reticle, 0.090 inch thick, including data fracture of up to 4 die per layer, defect inspection and repair, barcode generation. 2.0 micron minimum critical dimension, tolerance  $\pm 0.25$  micron, range 0.25 micron, address size 0.50 micron, registration  $\pm 0.25$  micron.

    0001AC Charge per extra data file conversion above 4 die per layer, to include extra data fractures, placement of each data file in proper location on the reticle, and inspections as required.

    0001AD Double sided pellicle as required and in accordance with section C.

    0001AE Repellicization, as required, in accordance with section C.

0002    Photolithographic masks for Karl SUSS MA150CC Aligner, consisting of:

    0002AA Mask, 0.150 inch thick, including data fracture of up to 4 die per layer, defect inspection and repair. 10.0 micron minimum critical dimension, tolerance  $\pm 0.50$  micron, range 0.50 micron, address size 0.50 micron, registration  $\pm 0.25$  micron.

    0002AB Mask, 0.150 inch thick, including data fracture of up to 4 die per layer, defect inspection and repair. 2.0 micron minimum critical dimension, tolerance  $\pm 0.20$  micron, range 0.25 micron, address size 0.25 micron, registration  $\pm 0.25$  micron.

    0002AC Charge per extra data file conversion above 4 die per layer, to include extra data fractures, placement of each data file in proper location on the mask, and inspections as required.

0003    Photolithographic reticles for Canon FPA-3000EX4 stepper, consisting of:

    0003AA Reticle, 0.250 inch thick, including data fracture of up to 4 die per layer, defect inspection and repair, barcode generation. 1.25 micron minimum critical dimension, tolerance  $\pm 0.125$  micron, range 0.125 micron, address size 0.25 micron, registration  $\pm 0.25$  micron.

    0003AB Reticle, 0.250 inch thick, including data fracture of up to 4 die per layer, defect inspection and repair, barcode generation. 1.25 micron minimum critical dimension, tolerance  $\pm 0.05$  micron, range 0.075 micron, address size 0.25 micron, registration  $\pm 0.15$  micron.

    0003AC Charge per extra data file conversion above 4 die per layer, to include extra data fractures, placement of each data file in proper location on the mask, and inspections as required.

    0003AD Double sided pellicle as required and in accordance with section C.

    0003AE Repellicization, as required, in accordance with section C.

0004    Data ISW CDRL, DD1423, Exhibit A

Option Year One:

0005 Photolithographic masks for GCA XLS Model 7300 I-line stepper, consisting of:

0005AA Reticle, 0.090 inch thick, including data fracture of up to 4 die per layer, defect inspection and repair, barcode generation. 2.0 micron minimum critical dimension, tolerance  $\pm 0.25$  micron, range 0.25 micron, address size 0.20 micron, registration  $\pm 0.25$  micron.

0005AB Reticle, 0.090 inch thick, including data fracture of up to 4 die per layer, defect inspection and repair, barcode generation. 2.0 micron minimum critical dimension, tolerance  $\pm 0.25$  micron, range 0.25 micron, address size 0.50 micron, registration  $\pm 0.25$  micron.

0005AC Charge per extra data file conversion above 4 die per layer, to include extra data fractures, placement of each data file in proper location on the reticle, and inspections as required.

0005AD Double sided pellicle as required and in accordance with section C.

0005AE Repellicization, as required, in accordance with section C.

0006 Photolithographic masks for Karl SUSS MA150CC Aligner, consisting of:

0006AA Mask, 0.150 inch thick, including data fracture of up to 4 die per layer, defect inspection and repair. 10.0 micron minimum critical dimension, tolerance  $\pm 0.50$  micron, range 0.50 micron, address size 0.50 micron, registration  $\pm 0.25$  micron.

0006AB Mask, 0.150 inch thick, including data fracture of up to 4 die per layer, defect inspection and repair. 2.0 micron minimum critical dimension, tolerance  $\pm 0.20$  micron, range 0.25 micron, address size 0.25 micron, registration  $\pm 0.25$  micron.

0006AC Charge per extra data file conversion above 4 die per layer, to include extra data fractures, placement of each data file in proper location on the mask, and inspections as required.

0007 Photolithographic masks for Canon FPA-3000EX4 stepper, consisting of:

0007AA Reticle, 0.250 inch thick, including data fracture of up to 4 die per layer, defect inspection and repair, barcode generation. 1.25 micron minimum critical dimension, tolerance  $\pm 0.125$  micron, range 0.125 micron, address size 0.25 micron, registration  $\pm 0.25$  micron.

0007AB Reticle, 0.250 inch thick, including data fracture of up to 4 die per layer, defect inspection and repair, barcode generation. 1.25 micron minimum critical dimension, tolerance  $\pm 0.05$  micron, range 0.075 micron, address size 0.25 micron, registration  $\pm 0.15$  micron.

0007AC Charge per extra data file conversion above 4 die per layer, to include extra data fractures, placement of each data file in proper location on the mask, and inspections as required.

0007AD Double sided pellicle as required and in accordance with section C.

0007AE Repellicization, as required, in accordance with section C.

0008 Data ISW CDRL, DD1423, Exhibit A

Option Year Two:

0009 Photolithographic masks for GCA XLS Model 7300 I-line stepper, consisting of:

0009AA Reticle, 0.090 inch thick, including data fracture of up to 4 die per layer, defect inspection and repair, barcode generation. 2.0 micron minimum critical dimension, tolerance  $\pm 0.25$  micron, range 0.25 micron, address size 0.20 micron, registration  $\pm 0.25$  micron.

0009AB Reticle, 0.090 inch thick, including data fracture of up to 4 die per layer, defect inspection and repair, barcode generation. 2.0 micron minimum critical dimension, tolerance  $\pm 0.25$  micron, range 0.25 micron, address size 0.50 micron, registration  $\pm 0.25$  micron.

0009AC Charge per extra data file conversion above 4 die per layer, to include extra data fractures, placement of each data file in proper location on the reticle, and inspections as required.

0009AD Double sided pellicle as required and in accordance with section C.

0009AE Repellicization, as required, in accordance with section C.

0010 Photolithographic masks for Karl SUSS MA150CC Aligner, consisting of:

0010AA Mask, 0.150 inch thick, including data fracture of up to 4 die per layer, defect inspection and repair. 10.0 micron minimum critical dimension, tolerance  $\pm 0.50$  micron, range 0.50 micron, address size 0.50 micron, registration  $\pm 0.25$  micron.

0010AB Mask, 0.150 inch thick, including data fracture of up to 4 die per layer, defect inspection and repair. 2.0 micron minimum critical dimension, tolerance  $\pm 0.20$  micron, range 0.25 micron, address size 0.25 micron, registration  $\pm 0.25$  micron.

0010AC Charge per extra data file conversion above 4 die per layer, to include extra data fractures, placement of each data file in proper location on the mask, and inspections as required.

0011 Photolithographic masks for Canon FPA-3000EX4 stepper, consisting of:

0011AA Reticle, 0.250 inch thick, including data fracture of up to 4 die per layer, defect inspection and repair, barcode generation. 1.25 micron minimum critical dimension, tolerance  $\pm 0.125$  micron, range 0.125 micron, address size 0.25 micron, registration  $\pm 0.25$  micron.

0011AB Reticle, 0.250 inch thick, including data fracture of up to 4 die per layer, defect inspection and repair, barcode generation. 1.25 micron minimum critical dimension, tolerance  $\pm 0.05$  micron, range 0.075 micron, address size 0.25 micron, registration  $\pm 0.15$  micron.

0011AC Charge per extra data file conversion above 4 die per layer, to include extra data fractures, placement of each data file in proper location on the mask, and inspections as required.

0011AD Double sided pellicle as required and in accordance with section C.

0011AE Repellicization, as required, in accordance with section C.

0012 Data ISW CDRL, DD1423, Exhibit A

Option Year Three:

0013 Photolithographic masks for GCA XLS Model 7300 I-line stepper, consisting of:

0013AA Reticle, 0.090 inch thick, including data fracture of up to 4 die per layer, defect inspection and repair, barcode generation. 2.0 micron minimum critical dimension, tolerance  $\pm 0.25$  micron, range 0.25 micron, address size 0.20 micron, registration  $\pm 0.25$  micron.

0013AB Reticle, 0.090 inch thick, including data fracture of up to 4 die per layer, defect inspection and repair, barcode generation. 2.0 micron minimum critical dimension, tolerance  $\pm 0.25$  micron, range 0.25 micron, address size 0.50 micron, registration  $\pm 0.25$  micron.

0013AC Charge per extra data file conversion above 4 die per layer, to include extra data fractures, placement of each data file in proper location on the reticle, and inspections as required.

0013AD Double sided pellicle as required and in accordance with section C.

0013AE Repellicization, as required, in accordance with section C.

0014 Photolithographic masks for Karl SUSS MA150CC Aligner, consisting of:

0014AA Mask, 0.150 inch thick, including data fracture of up to 4 die per layer, defect inspection and repair. 10.0 micron minimum critical dimension, tolerance  $\pm 0.50$  micron, range 0.50 micron, address size 0.50 micron, registration  $\pm 0.25$  micron.

0014AB Mask, 0.150 inch thick, including data fracture of up to 4 die per layer, defect inspection and repair. 2.0 micron minimum critical dimension, tolerance  $\pm 0.20$  micron, range 0.25 micron, address size 0.25 micron, registration  $\pm 0.25$  micron.

0014AC Charge per extra data file conversion above 4 die per layer, to include extra data fractures, placement of each data file in proper location on the mask, and inspections as required.

0015 Photolithographic masks for Canon FPA-3000EX4 stepper, consisting of:

0015AA Reticle, 0.250 inch thick, including data fracture of up to 4 die per layer, defect inspection and repair, barcode generation. 1.25 micron minimum critical dimension, tolerance  $\pm 0.125$  micron, range 0.125 micron, address size 0.25 micron, registration  $\pm 0.25$  micron.

0015AB Reticle, 0.250 inch thick, including data fracture of up to 4 die per layer, defect inspection and repair, barcode generation. 1.25 micron minimum critical dimension, tolerance  $\pm 0.05$  micron, range 0.075 micron, address size 0.25 micron, registration  $\pm 0.15$  micron.

0015AC Charge per extra data file conversion above 4 die per layer, to include extra data fractures, placement of each data file in proper location on the mask, and inspections as required.

0015AD Double sided pellicle as required and in accordance with section C.

0015AE Repellicization, as required, in accordance with section C.

0016 Data ISW CDRL, DD1423, Exhibit A

Option Year Four:

0017 Photolithographic masks for GCA XLS Model 7300 I-line stepper, consisting of:

0017AA Reticle, 0.090 inch thick, including data fracture of up to 4 die per layer, defect inspection and repair, barcode generation. 2.0 micron minimum critical dimension, tolerance  $\pm 0.25$  micron, range 0.25 micron, address size 0.20 micron, registration  $\pm 0.25$  micron.

0017AB Reticle, 0.090 inch thick, including data fracture of up to 4 die per layer, defect inspection and repair, barcode generation. 2.0 micron minimum critical dimension, tolerance  $\pm 0.25$  micron, range 0.25 micron, address size 0.50 micron, registration  $\pm 0.25$  micron.

0017AC Charge per extra data file conversion above 4 die per layer, to include extra data fractures, placement of each data file in proper location on the reticle, and inspections as required.

0017AD Double sided pellicle as required and in accordance with section C.

0017AE Repellicization, as required, in accordance with section C.

0018 Photolithographic masks for Karl SUSS MA150CC Aligner, consisting of:

0018AA Mask, 0.150 inch thick, including data fracture of up to 4 die per layer, defect inspection and repair. 10.0 micron minimum critical dimension, tolerance  $\pm 0.50$  micron, range 0.50 micron, address size 0.50 micron, registration  $\pm 0.25$  micron.

0018AB Mask, 0.150 inch thick, including data fracture of up to 4 die per layer, defect inspection and repair. 2.0 micron minimum critical dimension, tolerance  $\pm 0.20$  micron, range 0.25 micron, address size 0.25 micron, registration  $\pm 0.25$  micron.

0018AC Charge per extra data file conversion above 4 die per layer, to include extra data fractures, placement of each data file in proper location on the mask, and inspections as required.

0019 Photolithographic masks for Canon FPA-3000EX4 stepper, consisting of:

0019AA Reticle, 0.250 inch thick, including data fracture of up to 4 die per layer, defect inspection and repair, barcode generation. 1.25 micron minimum critical dimension, tolerance  $\pm 0.125$  micron, range 0.125 micron, address size 0.25 micron, registration  $\pm 0.25$  micron.

0019AB Reticle, 0.250 inch thick, including data fracture of up to 4 die per layer, defect inspection and repair, barcode generation. 1.25 micron minimum critical dimension, tolerance  $\pm 0.05$  micron, range 0.075 micron, address size 0.25 micron, registration  $\pm 0.15$  micron.

0019AC Charge per extra data file conversion above 4 die per layer, to include extra data fractures, placement of each data file in proper location on the mask, and inspections as required.

0019AD Double sided pellicle as required and in accordance with section C.

0019AE Repellicization, as required, in accordance with section C.

0020 Data ISW CDRL, DD1423, Exhibit A

NOTE REGARDING QUANTITIES: The following represents the estimated quantities by subline item, that will be used for evaluation purposes ONLY in order to determine the maximum ceiling amount of the contract. The contract award will establish unit prices for each CLIN and the government will place orders based on need.

<u>SUBLINE ITEM</u>	<u>ESTIMATED QTY</u>	<u>UNIT PRICE</u>	<u>TOTAL AMOUNT</u>
<u>Base Year</u>			
0001AA	40 EA	\$ _____	\$ _____
0001AB	10 EA	\$ _____	\$ _____
0001AC	0 EA	\$ _____	\$ _____
0001AD	50 EA	\$ _____	\$ _____
0001AE	0 EA	\$ _____	\$ _____
0002AA	10 EA	\$ _____	\$ _____
0002AB	0 EA	\$ _____	\$ _____
0002AC	0 EA	\$ _____	\$ _____
0003AA	35 EA	\$ _____	\$ _____
0003AB	20 EA	\$ _____	\$ _____
0003AC	0 EA	\$ _____	\$ _____
0003AD	50 EA	\$ _____	\$ _____
0003AE	5 EA	\$ _____	\$ _____
0004		NSP	NSP
Total Base Year			\$ _____
<u>Option Year 1</u>			
0005AA	40 EA	\$ _____	\$ _____
0005AB	10 EA	\$ _____	\$ _____
0005AC	0 EA	\$ _____	\$ _____
0005AD	50 EA	\$ _____	\$ _____
0005AE	0 EA	\$ _____	\$ _____
0006AA	10 EA	\$ _____	\$ _____
0006AB	0 EA	\$ _____	\$ _____
0006AC	0 EA	\$ _____	\$ _____
0007AA	35 EA	\$ _____	\$ _____
0007AB	20 EA	\$ _____	\$ _____
0007AC	0 EA	\$ _____	\$ _____
0007AD	50 EA	\$ _____	\$ _____
0007AE	5 EA	\$ _____	\$ _____
0008	NSP	NSP	
Total Option Year 1			\$ _____

Option Year 2

0009AA	40 EA	\$ _____	\$ _____
0009AB	10 EA	\$ _____	\$ _____
0009AC	0 EA	\$ _____	\$ _____
0009AD	50 EA	\$ _____	\$ _____
0009AE	0 EA	\$ _____	\$ _____
0010AA	10 EA	\$ _____	\$ _____
0010AB	0 EA	\$ _____	\$ _____
0010AC	0 EA	\$ _____	\$ _____
0011AA	35 EA	\$ _____	\$ _____
0011AB	20 EA	\$ _____	\$ _____
0011AC	0 EA	\$ _____	\$ _____
0011AD	50 EA	\$ _____	\$ _____
0011AE	5 EA	\$ _____	\$ _____
0012		NSP	NSP

Total Option Year 2 \$ \_\_\_\_\_

Option Year 3

0013AA	40 EA	\$ _____	\$ _____
0013AB	10 EA	\$ _____	\$ _____
0013AC	0 EA	\$ _____	\$ _____
0013AD	50 EA	\$ _____	\$ _____
0013AE	0 EA	\$ _____	\$ _____
0014AA	10 EA	\$ _____	\$ _____
0014AB	0 EA	\$ _____	\$ _____
0014AC	0 EA	\$ _____	\$ _____
0015AA	35 EA	\$ _____	\$ _____
0015AB	20 EA	\$ _____	\$ _____
0015AC	0 EA	\$ _____	\$ _____
0015AD	50 EA	\$ _____	\$ _____
0015AE	5 EA	\$ _____	\$ _____
0016	NSP	NSP	

Total Option Year 3 \$ \_\_\_\_\_

Option Year 4

0017AA	40 EA	\$ _____	\$ _____
0017AB	10 EA	\$ _____	\$ _____
0017AC	0 EA	\$ _____	\$ _____
0017AD	50 EA	\$ _____	\$ _____
0017AE	0 EA	\$ _____	\$ _____

0018AA	10 EA	\$ _____	\$ _____
0018AB	0 EA	\$ _____	\$ _____
0018AC	0 EA	\$ _____	\$ _____

0019AA	35 EA	\$ _____	\$ _____
0019AB	20 EA	\$ _____	\$ _____
0019AC	0 EA	\$ _____	\$ _____
0019AD	50 EA	\$ _____	\$ _____
0019AE	5 EA	\$ _____	\$ _____

0020	NSP	NSP	
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Total Option Year 4 \$ \_\_\_\_\_

**Exhibit A**  
Contract Data Requirements List

**CONTRACT DATA REQUIREMENTS LIST**  
**(2 Data Item)**

**Form Approved**  
**OMB No. 0704-0188**

Public reporting burden for this collection of information is estimated to average 110 hours per response, including the time for reviewing instructions, searching existing data sources, gathering and maintaining the data needed, and completing and reviewing the collection of information. Send comments regarding this burden estimate or any other aspect of this collection of information, including suggestions for reducing this burden, to Department of Defense, Washington Headquarters Services, Directorate for Information Operations and Reports, 1215 Jefferson Davis Highway, Suite 1204, Arlington, VA 22202-4302, and to the Office of Management and Budget, Paperwork Reduction Project (0704-0188), Washington, DC 20503. Please DO NOT RETURN your form to either of these addresses. Send completed form to the Government Issuing Contract Officer for the Contract/PR No. listed in Block E.

<b>A. CONTRACT LINE ITEM NO.</b>		<b>B. EXHIBIT</b> A		<b>C. CATEGORY:</b> TDP                      TM                      OTHER                      MISC					
<b>D. SYSTEM/ITEM</b> PHOTOLITHOGRAPHIC MASKS			<b>E. CONTRACT/PR NO.</b> /		<b>F. CONTRACTOR</b>				
<b>1. DATA ITEM NO.</b> A001		<b>2. TITLE OF DATA ITEM</b> Technical Report-Study/Services			<b>3. SUBTITLE</b> Reticle Summary Reports				
<b>4. AUTHORITY</b> DI-MISC-80508			<b>5. CONTRACT REFERENCE</b> SOW Para 3.5		<b>6. REQUIRING OFFICE</b> SPAWARSYSCEN SAN DIEGO 2876				
<b>7. DD250 REQ</b> LT	<b>9. DIST STATEMENT</b> See Attachment 1		<b>10. FREQUENCY</b> ASREQ	<b>12. FIRST SUBMISSION</b> SEE BLK 16		<b>14. DISTRIBUTION</b>			
<b>8. APP CODE</b> N/A			<b>11. AS OF DATE</b> N/A	<b>13. SUBSEQUENT SUBMISSION</b> SEE BLK 16		<b>a. ADDRESSEE</b>			
<b>16. REMARKS</b> Blk 4: Contractor format authorized. Include standard commercial documentation and any inspection, centrality, defect maps and reports related to each reticle.  Blks 12 & 13: As required, NLT EOC.  Blks 14: Deliver electronically to each addressee via email.  Code 2876: houssaye@spawar.navy.mil Code 2213: cdrl@spawar.navy.mil							<b>b. COPIES</b>		
								<b>Final</b>	
							<b>Draft</b>	<b>Reg</b>	<b>Repro</b>
						M/F CODE 2876	0	1	0
M/F CODE 2213	0	1	0						
						<b>15. Total ----&gt;</b>	0	2	0

<b>G. PREPARED BY</b> PAUL DELAHOUSAYE	<b>H. DATE</b> 01/24/2002	<b>I. APPROVED BY</b>  ROSAURO DELEON	<b>J. DATE</b> 04/16/2002
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ATTACHMENT 1  
DD-1423

THE CONTRACTOR SHALL APPLY THE FOLLOWING DISTRIBUTION STATEMENT TO EACH DELIVERABLE

**Do Not Distribute to DTIC or other data depositories**

Distribution Limited to DOD and DOD Contractors Only

Premature dissemination (date\* statement applied).

Other request shall be referred to:

**Commanding Officer  
SPACE AND NAVAL WARFARE SYSTEMS CENTER  
Code 20271  
SAN DIEGO, CA 92152-5001**

\*Proper date to be determined by Program Manager and affixed by contractor

Marking on documents shall be applied as follows:

Written or Printed Material with Covers and/or Title pages:	Statement printed, typed or stamped on front cover and title page.
Documents without Covers/Title pages:	Statement typed, printed or stamped on first page.
Drawings:	Statement typed, printed or stamped near title block.
Magnetic tape, cassette, or disk:	Statement typed, printed or stamped on a label affixed to outside of media. Also, the First and Last Pages or resulting hard-copy report or computer printout must be marked with the same statement as appears on the label.
Microfilm:	Statement typed, printed, or stamped on outside of jacket or canister housing the material. Also, the First and Last Pages of resulting hard-copy and the First and Last frames must be marked with the statement. Microfiche headers must contain an abbreviated version of the statement.